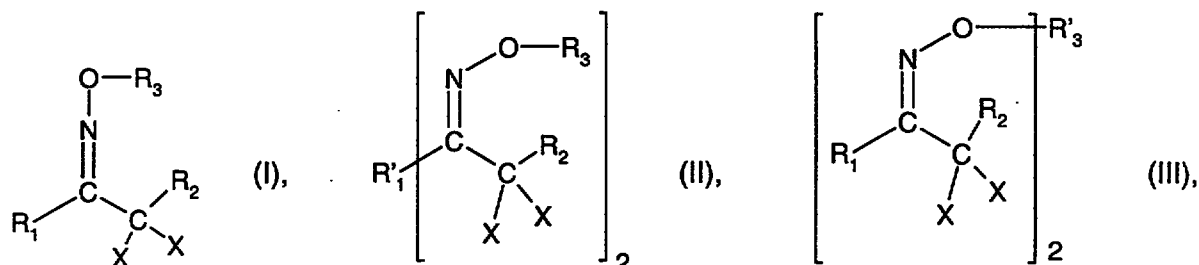


Abstract

Compounds of formula I, II and III, wherein



wherein R_1 is for example hydrogen, $\text{C}_1\text{-C}_{12}$ alkyl, $\text{C}_3\text{-C}_{30}$ cycloalkyl, $\text{C}_2\text{-C}_{12}$ alkenyl, $\text{C}_4\text{-C}_8$ cycloalkenyl, phenyl, which is unsubstituted or substituted, naphthyl, anthracyl or phenanthryl, unsubstituted or substituted, heteroaryl radical which is unsubstituted or substituted; wherein all radicals R_1 with the exception of hydrogen can additionally be substituted by a group having a -O-C -bond or a -O-Si -bond which cleaves upon the action of an acid; R'_1 is for example phenylene, naphthylene, diphenylene or oxydiphenylene, wherein these radicals are unsubstituted or substituted; R_2 is halogen or $\text{C}_1\text{-C}_{10}$ haloalkyl; R_3 is for example $\text{C}_1\text{-C}_{18}$ alkylsulfonyl, phenylsulfonyl, naphthylsulfonyl, anthracylsulfonyl or phenanthrylsulfonyl, wherein the groups are unsubstituted or substituted, or R_3 is e.g. $\text{C}_2\text{-C}_6$ haloalkanoyl, or halobenzoyl, R'_3 is for example phenylenedisulfonyl, naphthylenedisulfonyl, diphenylenedisulfonyl, or oxydiphenylenedisulfonyl, wherein these radicals are unsubstituted or substituted, X is halogen; are especially suitable as phototsensitive acid-donors in chemically amplified resist formulations.

This Sheet Has Been Replaced

